



SHEET 1 OF 1

<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>  (PTO-1449)				ATTY. DOCKET NO. <b>055071-0329</b>	SERIAL NO. <b>10/756,830</b>	
				<b>APPLICANT</b> <b>Doug van den BROEKE, et al.</b>		
				FILING DATE <b>January 14, 2004</b>	GROUP <b>2891</b>	
<b>U.S. PATENT DOCUMENTS</b>						
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code(s if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document		Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
<i>CYME</i>	US	5,895,741	04-20-1999	Hasegawa et al.		
	US	6,214,497 B1	04-10-2001	Stanton		
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EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number & Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes      No
<i>CYME</i>		EP 1 202 119 A1	05-02-2002	ASML Masktools B.V.		x
<i>CYME</i>		WO 03/054526 A1	07-03-2003	ADVANCED MICRO DEVICES, INC.		x
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>						
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				
<i>CYME</i>		Christoph DOLAINSKY, et al., "Simulation based method for sidelobe suppression," <i>Optical Microlithography XIII, Proceedings of SPIE</i> , 2000, pp 1156-1162, Vol. 4000				
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<i>CYME</i>		Douglas VAN DEN BROEKE, et al., "Near 0.3 k, Full Pitch Range Contact Hole Patterning Using Chromeless Phase Lithography (CPL)," <i>Proceedings of the SPIE</i> , September 9, 2003, pp 297-308, Vol. 5256, SPIE				
EXAMINER <i>C. Luerhart</i>			DATE CONSIDERED <i>11-11-06</i>			

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